

# Resource Summary Report

Generated by [dkNET](#) on Aug 17, 2026

## Oxford: PlasmaPro 80 PECVD Plasma Technology

RRID:SCR\_020380

Type: Tool

### Proper Citation

Oxford: PlasmaPro 80 PECVD Plasma Technology (RRID:SCR\_020380)

### Resource Information

**URL:** <https://plasma.oxinst.com/products/pecvd/plasmapro-80-pecvd>

**Proper Citation:** Oxford: PlasmaPro 80 PECVD Plasma Technology (RRID:SCR\_020380)

**Description:** PlasmaPro 80 is compact, small footprint system offering etch and deposition solutions with open loading. Open load design allows fast wafer loading and unloading, ideal for research, prototyping and low volume production. It enables high performance processes using optimised electrode cooling and substrate temperature control.

**Resource Type:** instrument resource

**Keywords:** Oxford, Plasma Technology, Instrument, Resource equipment, Equipment, USEdit,

**Availability:** Commercially available

**Resource Name:** Oxford: PlasmaPro 80 PECVD Plasma Technology

**Resource ID:** SCR\_020380

**Alternate IDs:** Model\_Number\_80\_PECVD

**Record Creation Time:** 20220129T080350+0000

**Record Last Update:** 20260815T182635+0000

### Ratings and Alerts

No rating or validation information has been found for Oxford: PlasmaPro 80 PECVD Plasma Technology.

No alerts have been found for Oxford: PlasmaPro 80 PECVD Plasma Technology.

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## Data and Source Information

**Source:** [SciCrunch Registry](#)

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## Usage and Citation Metrics

We have not found any literature mentions for this resource.